

ONERA

THE FRENCH AEROSPACE LAB

retour sur innovation

www.onera.fr



Displacement Damage Defect : Improving NIEL scaling

C. Inguibert, T. Nuns
ONERA- DESP, Toulouse center, France

C. Boatella-polo
CNES, Toulouse, France

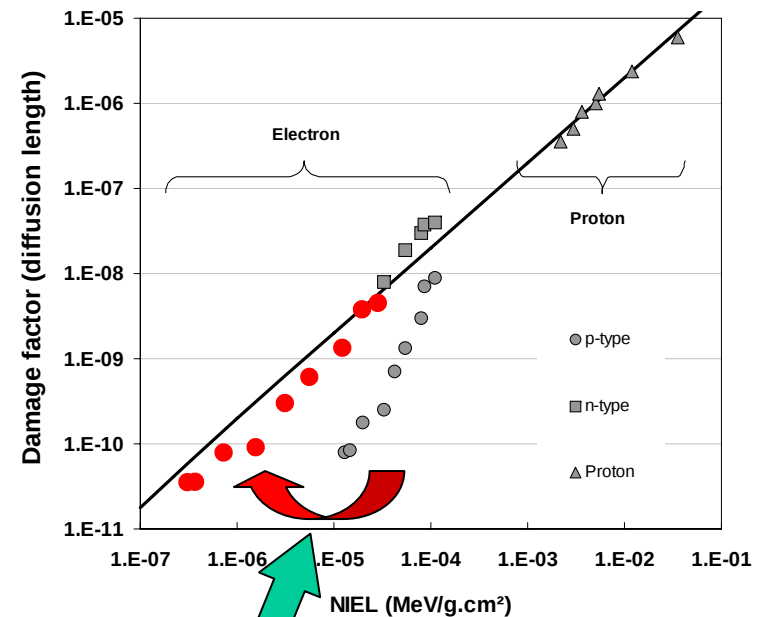
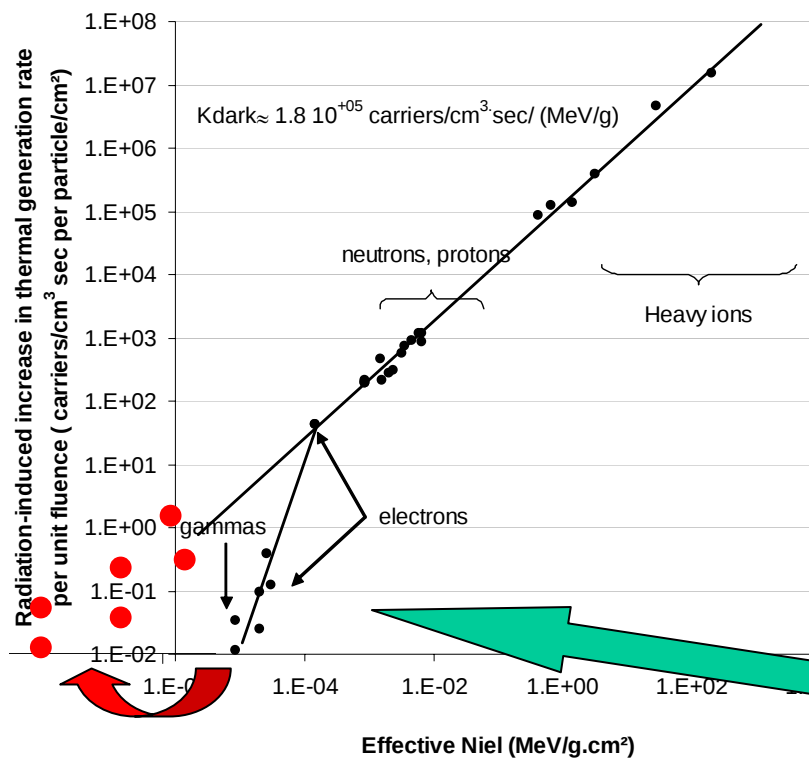


retour sur innovation



Introduction : NIEL scaling

- NIEL fails sometimes to predict degradation rate due to displacement damages



Quadratic variation

J. R. Srour, J. W. Palko " A framework for understanding displacement damage mechanisms in irradiated silicon devices," IEEE Trans. Nucl. Sci., vol. NS-53, no6, December 2006.

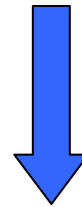
G. P. Summers, E. A. Burke, P. Shapiro, S. Messenger, R.J. Walters , IEEE Trans. Nucl. Sci., vol. 40, No. 6, pp. 1372-1379, December 1993.

C. Inguibert, P. Arnolda, T. Nuns, G. Rolland IEEE Trans. Nucl. Sci., vol. NS-57, no4, 2010

Goal

- Improving Displacement Damage degradation prediction
 - Improving NIEL
 - Improving Monte Carlo transport codes

BCA hypothesis



**Incorporating for displacement analysis
the "improved BCA" method in a GEANT 4
application**

Outline

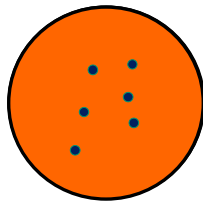
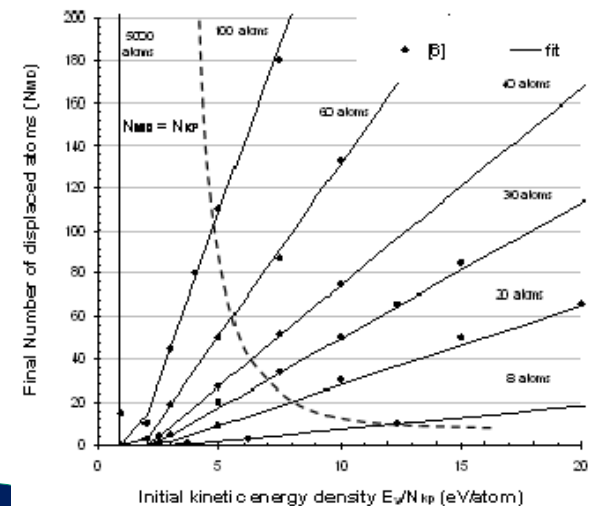
- Introduction
- NIEL improvement for **silicon**
 - Principle of the calculation
 - Comparison with measured defects introduction rates
- Conclusion
- Outlook

Amorphous pockets

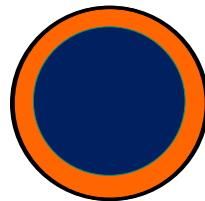
- Competition between melting and diffusion of energy processes
- Importance of deposited energy density Santos & al. [5, 6]
- Collective motion that allows displacement damages generation below the traditional threshold ($T_d \sim 21$ eV in Si)

BCA

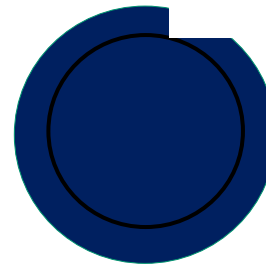
$$\text{Number of displacements} = 0.4 \frac{G(E)}{T_d}$$



1eV/atom



2eV/atom



5eV/atom



Size initial moving atoms

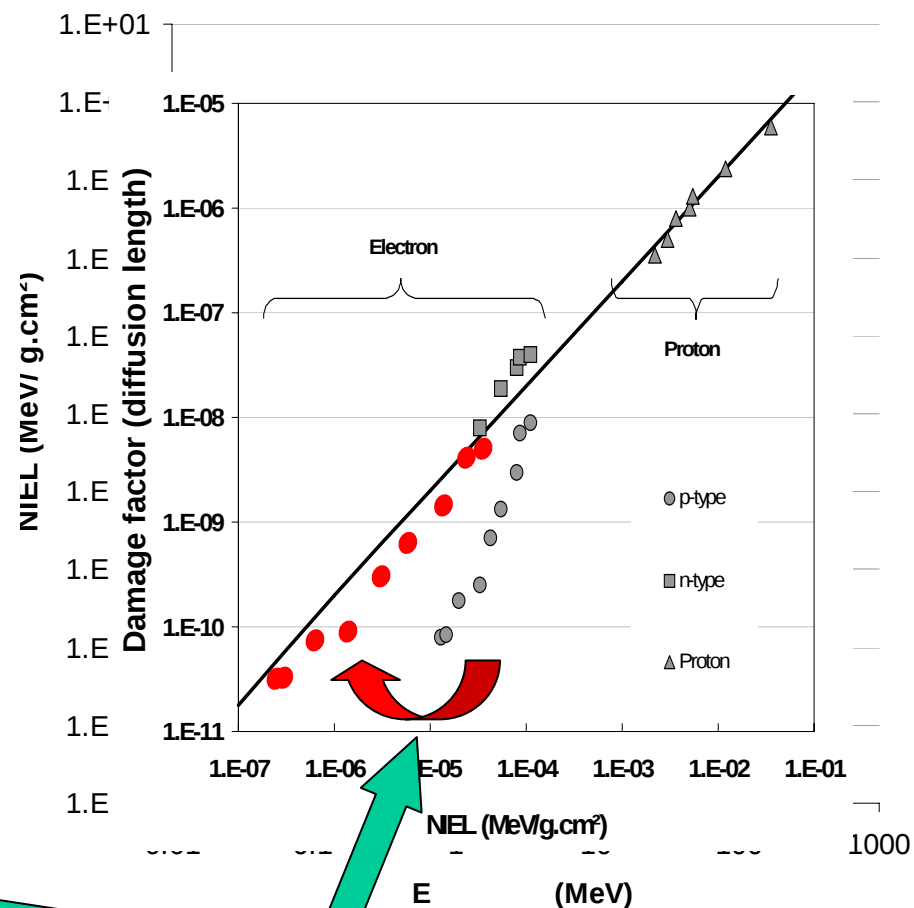
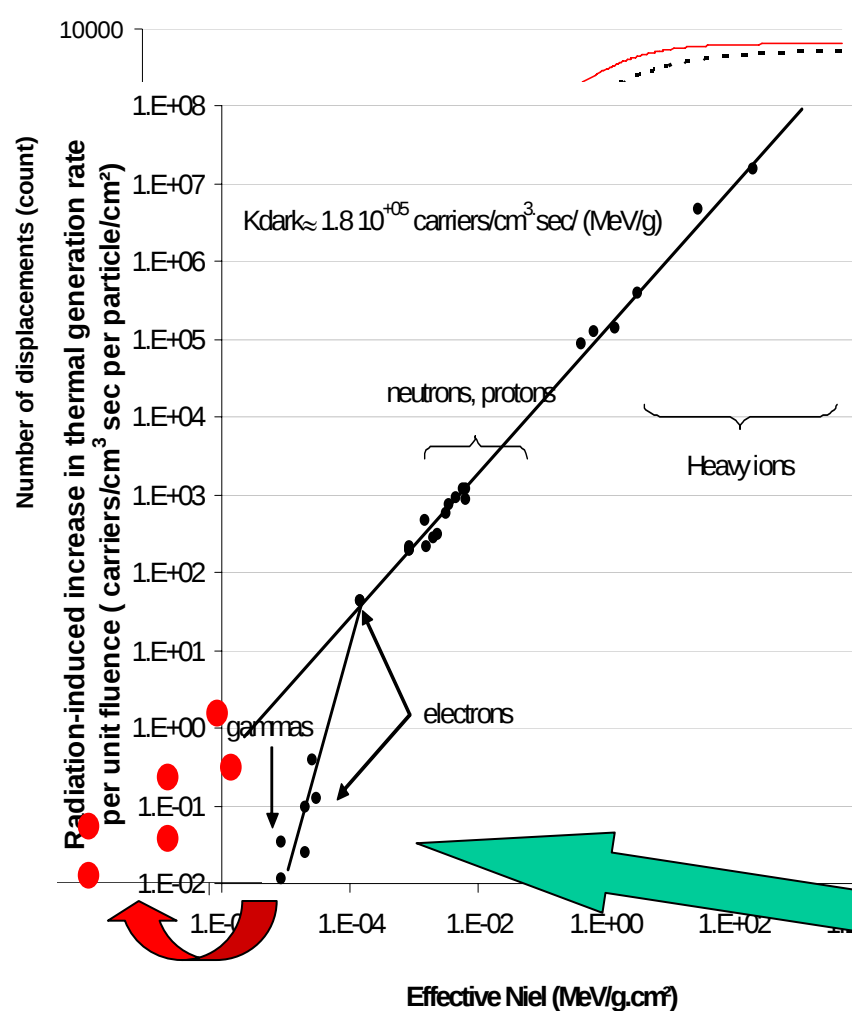


Size final pocket

[5] I. Santos, L. Marques, P. Lourdes, " Modeling of damage generation mechanisms in silicon at energies below the displacement threshold, " Physical Review B 74, 174115 (2006).

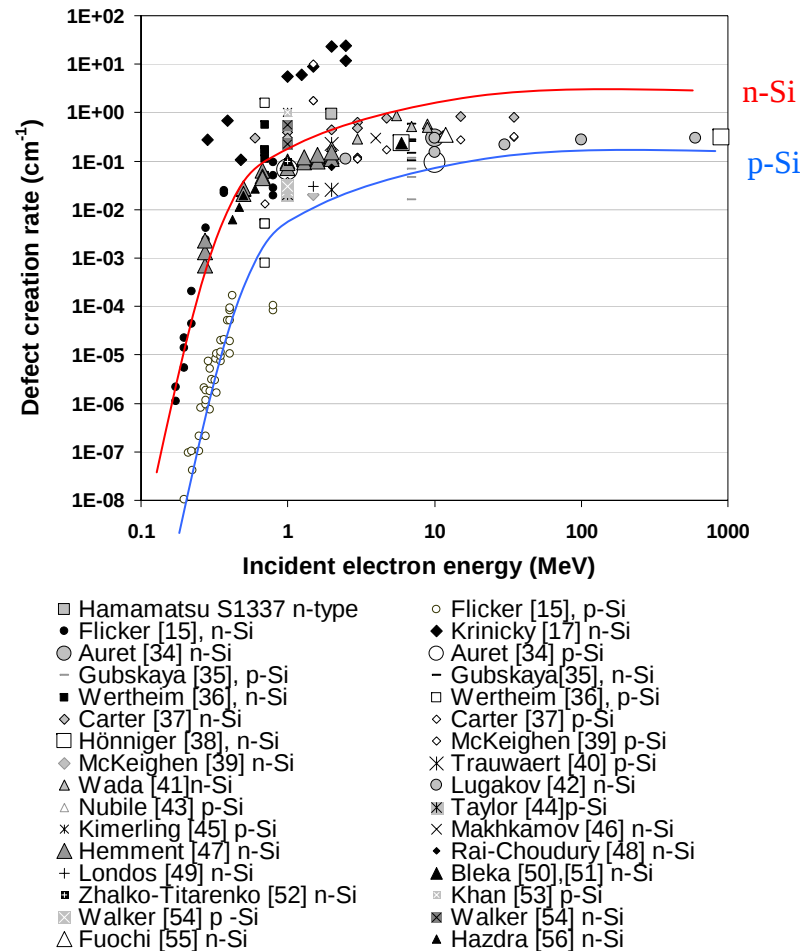
[6] I. Santos, L. Marques, P. Lourdes, P. Lopez, " Molecular dynamics study of damage generation mechanisms in silicon at the low energy regime, " Electron Devices, 2007 Spanish Conference on, pp. 37-40, 02 February 2007.

Amorphous pockets



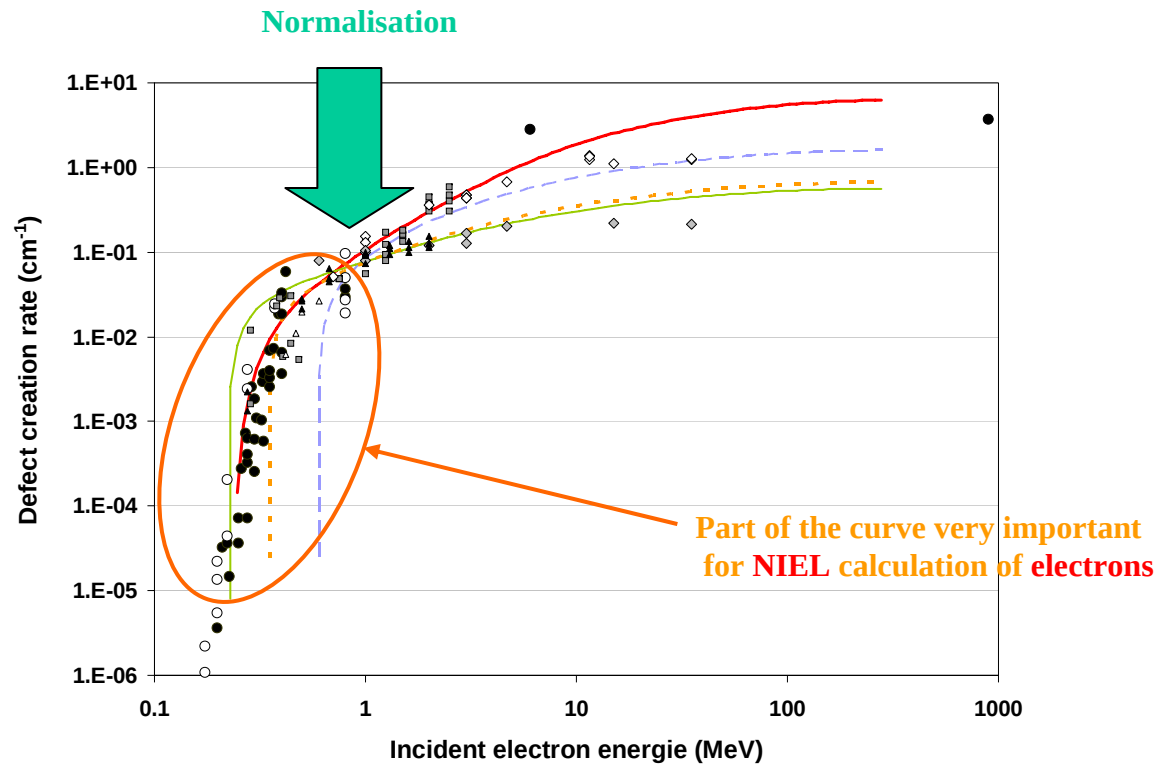
C. Inguibert, P. Arnold, T. Nuns, G. Rolland IEEE Trans. Nucl. Sci., vol. NS-57, no4, 2010

Bibliographic data : defects introduction rates for electrons in silicon



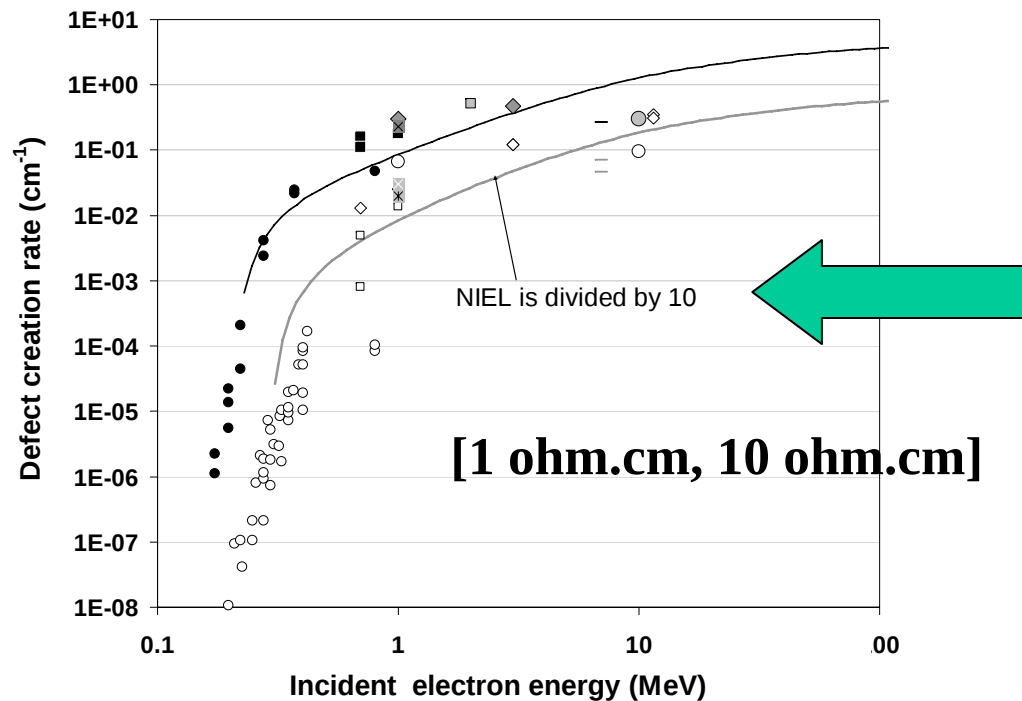
M. J. Beck, L. Tsetseris, M. Caussanel, R. D. Schrimpf, D. M. Fleetwood, and S. T. Plantelides, "Atomic scale Mechanisms for low-NIEL dopant-type dependent damage in Si, " IEEE Trans. Nucl. Sci., vol. NS-53, no6, pp. 1372-1379, December 2006.

New NIEL calculation

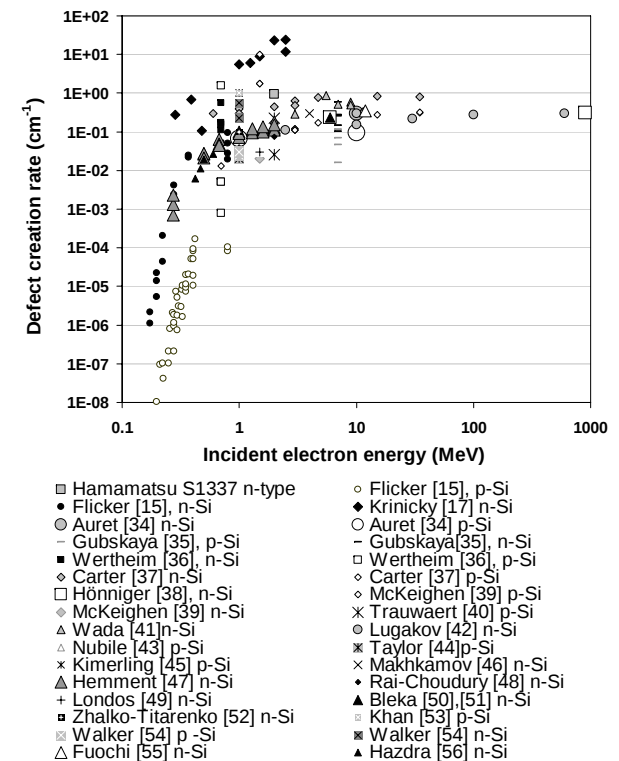


- — Kinchin Pease Td, KP = 72 eV
- Kinchin Pease, Td, KP = 21 eV
- Effective NIEL Td, MD = 1.8 eV
- - - Kinchin Pease, Td, KP = 36 eV

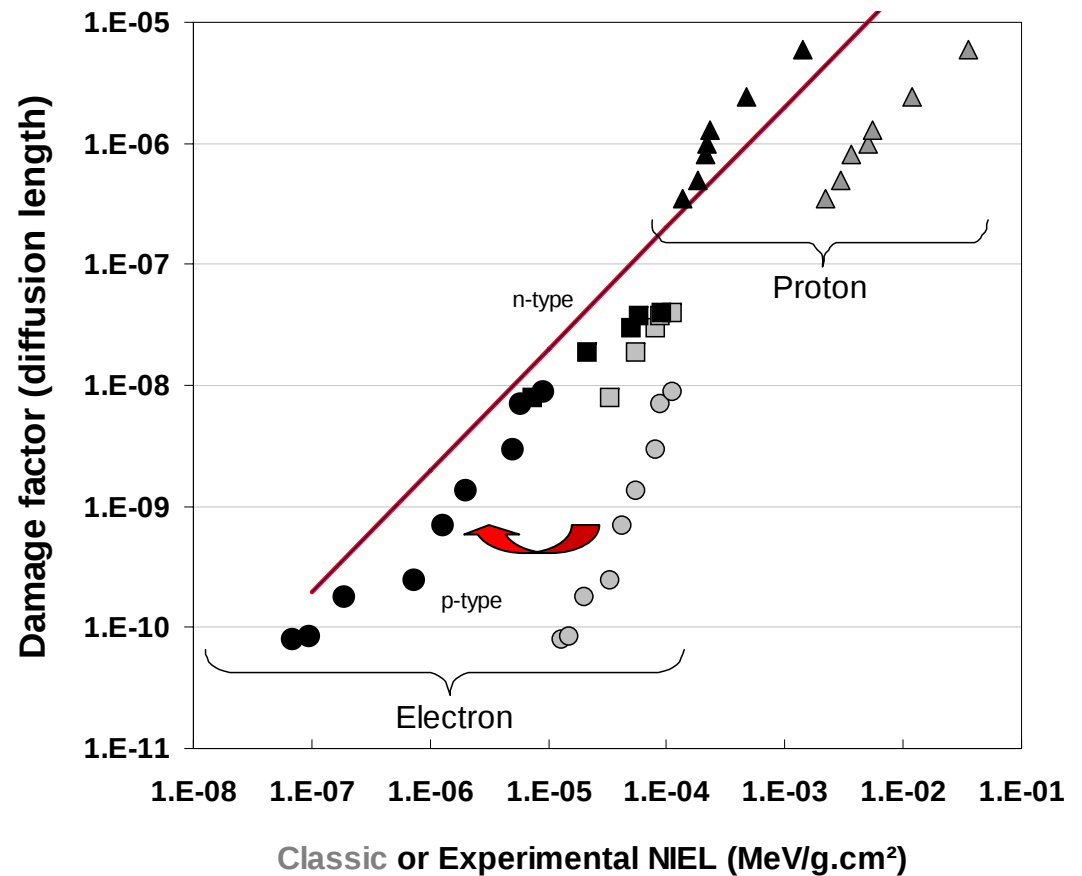
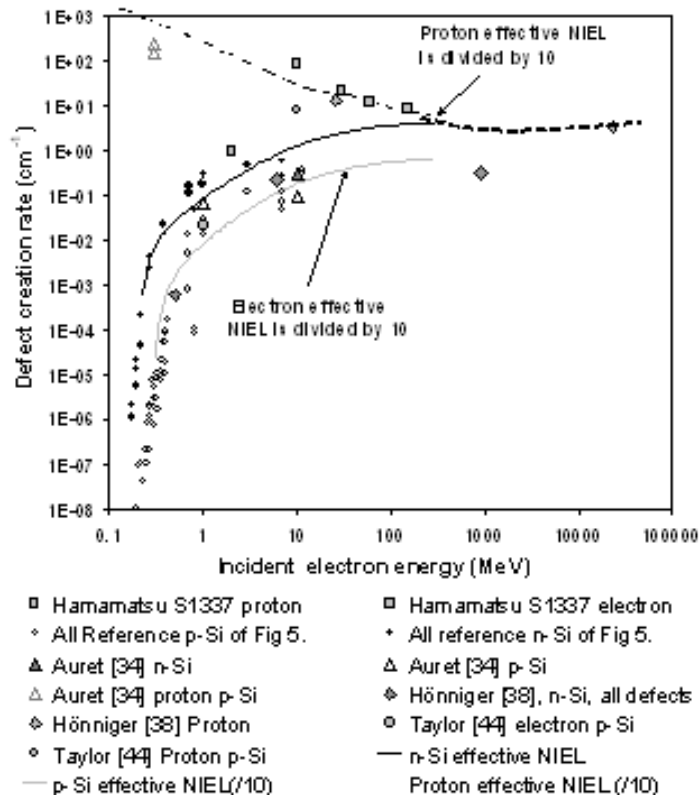
Defect introduction rate : comparison with experiments



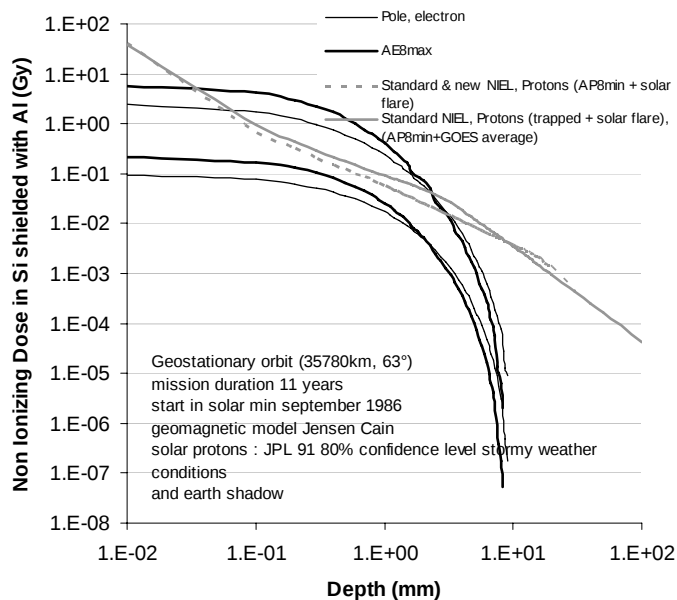
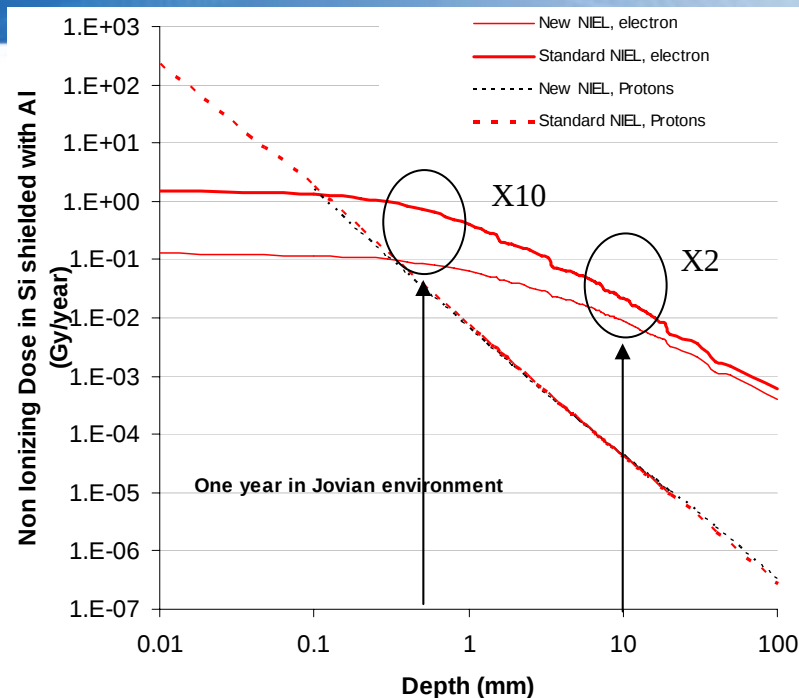
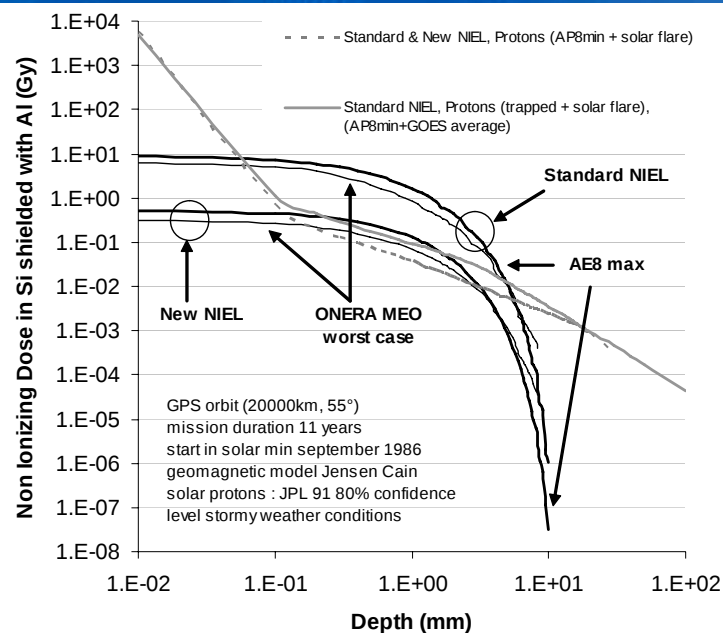
- Hamamatsu S1337-BQ
- Flicker [15], p-Si
- Auret [34] p-Si
- Gubskaya [35] p-Si
- Wertheim [36], p-Si
- ◇ Carter [37] p-Si
- ⊠ Walker [54] p-Si
- Effective NIEL [14] $T_d = 3\text{eV}$
- Flicker [15], n-Si
- Auret [34] n-Si
- Gubskaya [35] n-Si
- Wertheim [36], n-Si
- ◇ Carter [37] n-Si
- ⊠ Taylor [44] p-Si
- ⊠ Walker [54] n-Si
- Effective NIEL [14] $T_d = 1.6\text{ eV} (/10)$



Scaling degradation rate



Displacement Damage Dose profile



Electron constraint reduced between a factor 2 and a factor 10

Conclusion

Demonstrated for silicon

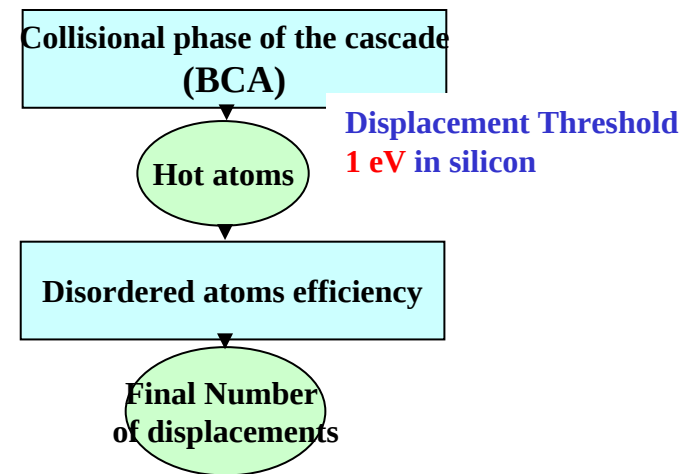
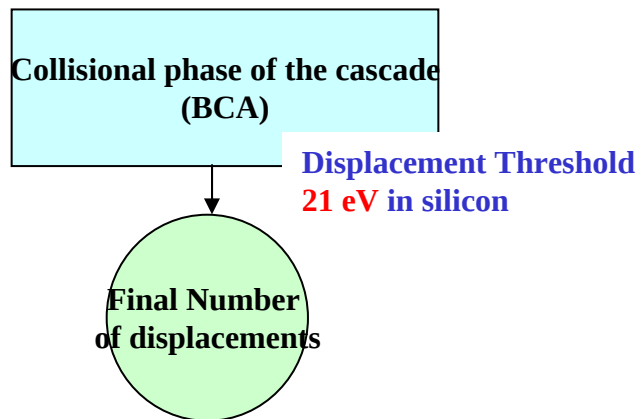
- Non linear effects, for low energy PKAs, (amorphous pockets)
- MD simulation are used to calculate a new energy partition function for Silicon and new NIEL (Electrons)
- Mixing calculation and defect introduction rate measurements leads to a better degradation prediction

Otlook : Improved BCA approach

Improving NIEL scaling method

Extending MD simulations for other materials (GaAs, InP, ...)
In order to define a new energy partition function and new NIELs tables

- **Monte Carlo (GEANT 4) implementation**



Perspectives : GEANT4 User Interface

- Incorporating the Improved BCA approach within a GEANT 4 user Interface
- Our own G4 interface demonstrator
 - Based on Input/Output file library

